

L Number	Hits	Search Text	DB	Time stamp
-	9047	427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/28 11:19
-	857	427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/29 08:12
-	444	& (impregnate impregnation impregnating impregnated) (427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/29 08:12
-	89	& (impregnate impregnation impregnating impregnated)) & (427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/27 12:56
-	5	& (impregnate impregnation impregnating impregnated)) & (vacuum)) & (porous with (substrate base article)) (((427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/27 13:19
-	84	& (impregnate impregnation impregnating impregnated)) & (vacuum)) & (porous with (substrate base article))) & (multiple with (steps chambers sections)) (((427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/29 08:09
-	9047	& (impregnate impregnation impregnating impregnated)) & (vacuum)) & (porous with (substrate base article))) not (((427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/28 11:19
-	384	& (impregnate impregnation impregnating impregnated)) & (vacuum)) & (porous with (substrate base article))) & (multiple with (steps chambers sections))) (427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/28 11:19
-	228	& ((impregnate impregnation impregnating impregnated) near3 (process method apparatus)) (427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/28 11:20
-	3	& ((impregnate impregnation impregnating impregnated) near3 (process method apparatus))) & (vacuum) ((427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/28 11:21
-	27	& ((impregnate impregnation impregnating impregnated) near3 (process method apparatus))) & (vacuum)) & (427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/28 11:21
-	29	& ((impregnate impregnation impregnating impregnated) near3 (process method apparatus))) & (vacuum)) & (porous near1 (substrate base article)) (((427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/28 11:21
-	84	& ((impregnate impregnation impregnating impregnated) near3 (process method apparatus))) & (vacuum)) & (427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/29 08:10
-	0	& (impregnate impregnation impregnating impregnated)) & (vacuum)) & (porous with (substrate base article))) not (((427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/29 08:12
-	444	& (impregnate impregnation impregnating impregnated)) & (vacuum)) & (porous with (substrate base article))) & (multiple with (steps chambers sections))) ) & (deareate with (427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/29 08:12
-	0	& (impregnate impregnation impregnating impregnated)) & (vacuum)) & (porous with (substrate base article))) & (427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/29 08:12
-	857	& (impregnate impregnation impregnating impregnated)) & (vacuum)) & (porous with (substrate base article))) & (multiple with (steps chambers sections))) ) & (deareate with (427/243,235,238,240,294,299,37.2,430.1,434.2;118/50,52,400,421.ccls.	423RAIE, EPO; JPO	2002/08/29 08:12

